

Abstract:

Projection lens, in particular for microlithography
(Figure 1)

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A projection lens (3), in particular for microlithography, is provided with an object plane (7), with an image plane (9), with a lens arrangement (4) and with at least one gas chamber filled with gas or through which gas flows. The gas chamber is
10 constructed as an approximately plane-parallel manipulation chamber (13). The refractive index can be varied in the manipulation chamber (13) by pressure changes and/or changes in gas composition.